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ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

HDP PROCESS FOR HIGH ASPECT RATIO GAP FILLING

Application Number:

Confirmation Number:

First Named Applicant:

Michael Belyansky

Attorney Docket Number:

FIS920030085

Art Unit:

Examiner:

Search string:

(6211040 or 6395450 or 6514837 or 6531377 or 20030003244 or 20030013270 or

20030013271 or 20030050724).pn

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Note: Applicant is not required to submit a paper copy of cited US Patent Documents

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Signature

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